

Amendments to the Claims

1. **(Currently Amended)** A substrate cleaning apparatus comprising:

a cleaning roller adapted to rotate and having a cleaning member adapted to be brought into contact with at least one of an end face and a bevel face of a substrate so as to perform scrub-cleaning to the at least one of the end face and the bevel face; and

a power transmission mechanism for transmitting a rotating force for rotating the substrate to the cleaning roller so as to rotate the cleaning roller; and

a contact location adjusting mechanism for vertically adjusting a contact location of the cleaning member with the substrate in a height direction of the cleaning member,

wherein the power transmission mechanism has a revolution transfer ratio set such that a relative difference in velocity exists between a peripheral velocity of revolution of the cleaning member and a peripheral velocity of revolution of the substrate.

2. **(Previously Presented)** A substrate cleaning apparatus of claim 1, further comprising a plurality of substrate rotating rollers for gripping the periphery of the substrate and rotating the substrate.

3. **(Previously Presented)** A substrate cleaning apparatus of claim 1, further comprising a cleaning nozzle for injecting a cleaning liquid against a surface of the cleaning member to be brought into contact with the substrate.

4. **(Previously Presented)** A substrate cleaning apparatus of claim 1, further comprising a force adjusting mechanism for adjusting an amount of pushing of the cleaning member against the at least one of the end face and the bevel face of the substrate.

5. **(Previously Presented)** A substrate cleaning apparatus of claim 1, further comprising a swingable swing arm rotatably supporting the cleaning roller on a free end thereof, wherein the swingable swing arm is biased in a direction of bringing the cleaning member into contact with the at least one of the end face and the bevel face of the substrate.

6. **(Canceled)**

7. **(Original)** A substrate cleaning apparatus of claim 2, further comprising a cleaning nozzle for injecting a cleaning liquid against a surface of the cleaning member to be brought into contact with the substrate.

8. **(Previously Presented)** A substrate cleaning apparatus of claim 2, further comprising a force adjusting mechanism for adjusting an amount of pushing of the cleaning member against the at least one of the end face and the bevel face of the substrate.

9. **(Previously Presented)** A substrate cleaning apparatus of claim 2, further comprising a swingable swing arm rotatably supporting the cleaning roller on a free end thereof, wherein the swingable swing arm is biased in a direction of bringing the cleaning member into contact with the at least one of the end face and the bevel face of the substrate.

10. **(Canceled)**

11. **(Previously Presented)** A substrate cleaning apparatus of claim 3, further comprising a force adjusting mechanism for adjusting an amount of pushing of the cleaning member against the at least one of the end face and the bevel face of the substrate.

12. **(Previously Presented)** A substrate cleaning apparatus of claim 3, further comprising a swingable swing arm rotatably supporting the cleaning roller on a free end thereof, wherein the swingable swing arm is biased in a direction of bringing the cleaning member into contact with the at least one of the end face and the bevel face of the substrate.

13. **(Canceled)**

14. **(Previously Presented)** A substrate cleaning apparatus of claim 4, further comprising a swingable swing arm rotatably supporting the cleaning roller on a free end thereof, wherein the swingable swing arm is biased in a direction of bringing the cleaning member into contact with the at least one of the end face and bevel face of the substrate.

15. **(Canceled)**

16. **(Canceled)**

17. **(Previously Presented)** A substrate cleaning apparatus comprising:

a pair of bases movable to come close to or to go away from each other;

a plurality of rollers supported on the bases, the rollers adapted to grip a periphery of a substrate;

a substrate rotating mechanism operable to rotate the rollers to thereby rotate the substrate;

a scrub-cleaning member supported on the bases, the scrub-cleaning member adapted to clean an end face of the substrate, and

a cleaning nozzle for directing a cleaning liquid between the scrub-cleaning member and the periphery of the substrate.

18. **(Previously Presented)** A substrate cleaning apparatus of claim 17, wherein the scrub-cleaning member comprises a cleaning roller which contacts the end face of the substrate.

19. **(Currently Amended)** A substrate cleaning apparatus of claim 18, wherein the substrate rotating mechanism transmits a rotating force to the cleaning roller-is.

20. **(Original)** A substrate cleaning apparatus of claim 17, further comprising a ultrasonic nozzle directing cleaning liquid to the end face of the substrate.

21. **(Previously Presented)** A substrate cleaning apparatus of claim 17, wherein each of the rollers has a groove into which the periphery of the substrate is to be inserted.